Contents

Series Preface *IX*
Volume Preface *XI*
List of Contributors *XIII*

1 Valve Metal, Si and Ceramic Oxides as Dielectric Films for Passive and Active Electronic Devices *1*

Alexander Michaelis

1.1 Introduction *1*
1.1.1 Experimental Approaches *2*
1.2 Fundamentals and Experimental Details *5*
1.2.1 Electrochemical Oxide Layer Formation on Valve Metals *5*
1.2.2 The $C(U)$ Curve of a Valve Metal Electrode *7*
1.2.3 Application of Lasers in Electrochemistry *8*
1.2.3.1 Thermal Effects *9*
1.2.4 Electrochemical Photocurrent Measurements (Optical/Electrical Method Class), Introduction of a New Model *10*
1.2.4.1 Photocurrent Model for Ultra-thin, Amorphous Films With TiO_2 as an Example *11*
1.3 Valve Metal Systems *15*
1.3.1 Ti/TiO_2 System *15*
1.3.1.1 Experimental Details *15*
1.3.1.2 Determination of Ti Substrate Grain Orientation by SAME *17*
1.3.1.3 Photocurrent Spectra and $i_{ph}(U)$ Measurements on Single Ti/TiO_2 Grains *18*
1.3.1.4 Microscopic Modification of the TiO_2 Films by Means of Laser Scanning *19*
1.3.1.5 Characterization of the Modified TiO_2 Films *21*
1.3.1.6 Photoresist Microelectrochemistry (Nanoliter Droplet Method) *25*
1.3.1.7 Applications of Photoresist Microelectrodes *28*
1.3.1.8 Summary and Conclusions for the Ti/TiO_2 System *36*

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1.3.2 Zr/ZrO_2 and Hf/HfO_2 Systems *37*
1.3.2.1 Zr/ZrO_2 *37*
1.3.2.2 Hf/HfO_2 *46*
1.3.3 Systems: Nb/Nb_2O_5, Ta/Ta_2O_5 and Al/Al_2O_3 *48*
1.3.3.1 Nb/Nb_2O_5 System *49*
1.3.3.2 Al/Al_2O_3 System *53*
1.3.3.3 Ta/Ta_2O_5 System *54*
1.3.4 Application of Valve Metals in Electrolytic Capacitor Manufacturing *57*
1.3.4.1 Capacitor Fundamentals *57*
1.3.4.2 Capacitor Device Types and Production of Ta Capacitors *62*
1.3.4.3 Current Development Trends for Ta Capacitors and Research Issues Involved *65*
1.3.4.4 Effect of Oxygen Content and Sinter Conditions on Dislocation Formation *67*
1.3.4.5 Thermal Runaway *70*
1.4 Si/SiO_2 System *74*
1.4.1 Application of the Si/SiO_2 System *77*
1.4.1.1 Si/SiO_2 in MOSFETs *77*
1.4.1.2 Si/SiO_2 in DRAMs *80*
1.4.1.3 DRAM Storage Capacitor (Deep Trench) *82*
1.4.2 Alternative Dielectric Materials *90*
1.4.2.1 Ta_2O_5 *92*
1.4.2.2 Ti/TiO_2 *95*
1.5 Summary and Conclusions *96*
References *99*

2 Superconformal Film Growth *107*
Thomas P. Moffat, Daniel Wheeler, and Daniel Josell
2.1 Introduction *107*
2.2 Destabilizing Influences *108*
2.3 Stabilization and Smoothing Mechanisms *110*
2.3.1 Geometric Leveling *110*
2.3.2 Inhibitor-based Leveling *110*
2.3.3 Brightening by Grain Refinement *111*
2.3.4 Catalyst-derived Brightening *112*
2.3.5 Stabilization Across Length Scales *112*
2.4 Additive Processes *113*
2.4.1 Adsorption Kinetics *117*
2.4.2 Surface Segregation versus Consumption Processes *117*
2.4.2.1 Adsorbates Segregated onto Growing Surface *118*
2.4.2.2 Adsorbates Incorporated into Growing Deposit *119*
2.4.2.3 Deactivation of Adsorbate *121*
2.4.3 Adsorbate Evolution *121*
2.4.4 Impact on Microstructure *122*
2.4.5 Quantifying Adsorbate Inhibition of Metal Deposition *125*

2.4.6 Co-adsorption Effects *130*
2.4.7 Catalysis of Metal Deposition *134*
2.4.8 Activation of Blocked Electrodes by Competitive Adsorption of a Catalyst *135*
2.4.9 Catalyst Function and Consumption *138*
2.4.10 Quantifying the Effects of Competitive Adsorption on Metal Deposition *141*
2.4.10.1 Site Dependence of Charge Transfer Kinetics *142*
2.4.10.2 Catalyst Evolution *143*
2.4.10.3 SPS Adsorption from the Electrolyte *143*
2.5 Interface Motion and Morphological Evolution *146*
2.5.1 Shape Change Simulations *146*
2.5.2 Geometric Leveling *150*
2.5.3 Inhibitor-based Leveling *153*
2.5.3.1 Feature Filling *153*
2.5.3.2 Stability Analysis *160*
2.5.4 Catalyst-derived Brightening *161*
2.5.4.1 Feature Filling *161*
2.5.4.2 Stability Analysis *173*
2.5.5 Bridging the Length Scales *176*
2.6 Conclusions and Outlook *179*
References *179*

3 Transition Metal Macrocycles as Electrocatalysts for Dioxygen Reduction *191*
Daniel A. Scherson, Attila Palencsár, Yuriy Tolmachev, and Ionel Stefan
3.1 Introduction *191*
3.1.1 Electrocatalysis *192*
3.1.2 Dioxygen Reduction in Aqueous Electrolytes: General Aspects *193*
3.1.3 Transition Metal Macrocycles *199*
3.1.3.1 General Characteristics *199*
3.1.3.2 Electrocatalytic Properties Toward Oxygen Reduction *201*
3.2 Homogeneous Electrocatalysis *204*
3.2.1 Intrinsic Properties of Solution Phase Transition Metal Macrocycles *204*
3.2.1.1 Formal Redox Potentials and Diffusion Coefficients *204*
3.2.1.2 Molecular Speciation *209*
3.2.1.3 Rates of Heterogeneous Electron Transfer Reactions *211*
3.2.2 Macrocyclic-Mediated Reduction of Dioxygen in Aqueous Electrolytes *212*
3.2.2.1 Model Systems *212*
3.3 Heterogeneous Electrocatalysis *219*
3.3.1 Adsorption Isotherms *220*
3.3.2 Chemically Modified Electrodes *221*
3.3.2.1 Preparation and Electrochemical Characterization *221*

3.3.2.2 *In situ* Spectroscopic Characterization *226*
3.3.3 Redox Active Chemically Modified Electrodes *232*
3.3.3.1 Thermodynamic Aspects *232*
3.3.3.2 Redox Speciation *235*
3.3.3.3 Redox Dynamics *238*
3.3.4 Electrocatalytic Aspects of Dioxygen Reduction *241*
3.3.4.1 Theoretical Considerations *241*
3.3.4.2 Model Systems *244*
3.4 Thermal Activation of Transition Metal Macrocycles *269*
3.4.1 Brief Introduction *269*
3.4.2 Electrochemical Characterization *269*
3.4.2.1 Cyclic Voltammetry *270*
3.4.2.2 Oxygen Reduction Polarization Curves *271*
3.4.3 Spectroscopic and Structural Characterization *273*
3.4.3.1 Pyrolysis-Mass Spectrometry *273*
3.4.3.2 Mossbauer Effect Spectroscopy *277*
3.4.3.3 X-ray Absorption Fine Structure *278*
3.4.3.4 X-ray Photoelectron Spectroscopy *281*
3.4.4 *In Situ* and Quasi *In Situ* Spectroscopic Characterization *281*
3.4.5 Concluding Remarks *283*
References *285*

4 Multiscale Modeling and Design of Electrochemical Systems *289*
Richard D. Braatz, Edmund G. Seebauer, and Richard C. Alkire
4.1 Introduction *289*
4.2 Background and Motivation *291*
4.2.1 Multiscale Simulation *291*
4.2.2 Electrochemical Systems *293*
4.2.3 Microelectronic Applications *295*
4.2.4 Nanoscale Science and Technology *296*
4.2.5 Other Electrochemical Applications *297*
4.3 Trend Toward Atomistic/Molecular Simulation *298*
4.3.1 Integrated Circuit Example *298*
4.3.2 Continuum Methods *300*
4.3.3 Molecular Simulation Methods *300*
4.3.4 Coarse-grained Simulation Methods *303*
4.4 Multiscale Simulation *304*
4.5 Challenges and Requirements of Multiscale Modeling *310*
4.6 Addressing the Challenges in Multiscale Modeling *311*
4.7 Design Based on Multiscale Models *315*
4.8 Concluding Remarks *322*
References *324*

Index *335*